

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2002-145954

(43)Date of publication of application : 22.05.2002

(51)Int.Cl.

C08F220/28  
C08K 5/00  
C08L 33/14  
G03F 7/039  
H01L 21/027

(21)Application number : 2000-343762

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(22)Date of filing : 10.11.2000

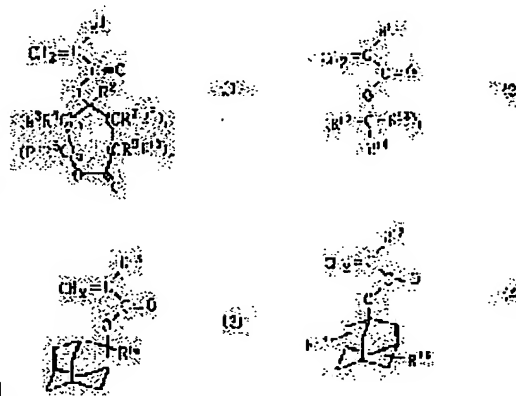
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## (54) POLYMER COMPOUND FOR PHOTORESIST AND METHOD FOR PRODUCING THE COMPOUND

## (57)Abstract:

**PROBLEM TO BE SOLVED:** To obtain a polymer compound for photoresist, containing uniformly distributed monomer units, having small intramolecular and intermolecular compositional distributions and exhibiting excellent etching resistance.

**SOLUTION:** The polymer compound for photoresist is produced by the copolymerization of a monomer mixture containing three kinds of (meth)acrylic acid esters comprising (A) a compound of formula 1, (B) a compound of formula 2 and/or 3 and (C) a (meth)acrylic acid ester of formula 4 having a substituted adamantane ring (R2, R12 and R13 are each H or a 1-3C hydrocarbon group; R14 is a 6-20C bridged alicyclic hydrocarbon group; R16 is methyl or the like; R18 and R19 are each H, hydroxy group, oxo group or carboxy group provided that R18 and R19 are not H at the same time; (p), (q), (r) and (s) are each 0 or 1; and p+q+r+s is 2-4).



## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's  
decision of rejection]

[Date of extinction of right]

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